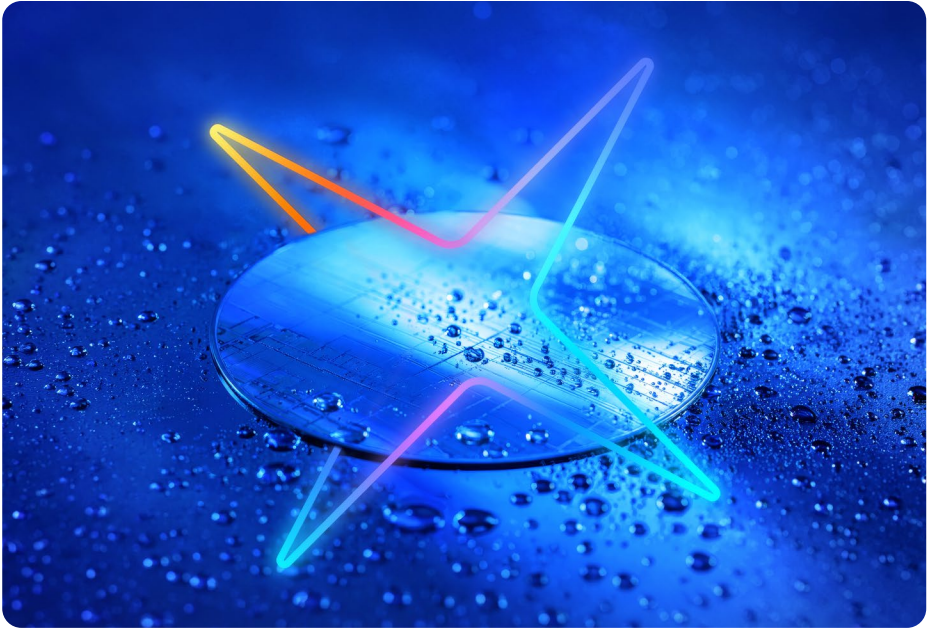




More AI Chips. Less Water.



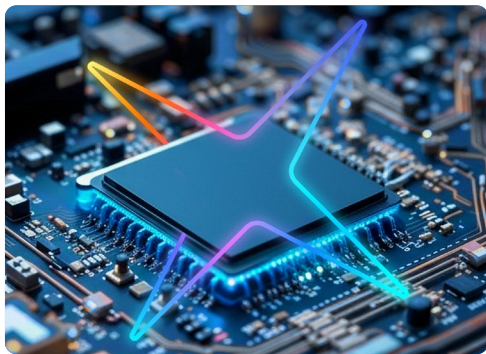
Meet the future of semiconductor manufacturing with the power of ultrapure water precision for increased wafer yield and quality; and full-cycle, integrated circularity to optimize water and energy efficiency.

OVIVO
Ultra-Pure Water +
by Ecolab

NALCO Water
An Ecolab Company



Water Technology Engineered for **Wafer Processing.**



UPW-Next™ Metal-Free Polishing Technologies

Protect Water Quality. Boost Wafer Yield.

UPW-Next™ introduces a new generation of metal-free polishing technologies designed to reduce contamination in ultrapure water systems, helping fabs protect water quality, maintain process stability and improve manufacturing performance. Fewer defects, better uptime, higher yield.

UPW-NEXT™ POLISHING REACTOR

Control ultra-low trace metals in advanced ultrapure water systems using metal-free final polishing reactor technology.



UPW-NEXT™ PUMPS

Metal-free ultrapure water pumps minimize contamination sources across ultrapure water transfer and distribution loops.



UPW-NEXT™ FILTER HOUSING

Engineered for final filtration in advanced ultrapure water systems.



Advanced real-time water analysis and automation

Transforming Water Data into Actionable Intelligence

From nanoparticle detection to real-time system monitoring and specialized contaminant analysis, our technologies give fabs improved visibility into water processes, enabling smarter decisions across ultrapure water, reclaim and utility systems.

NANOPULS™

Precise nanoparticle monitoring provides visibility down to the nanometer range.



UREA ANALYZER

Designed to detect and monitor urea contamination in high-purity water environments.



3D TRASAR™ TECHNOLOGY

A monitoring and control platform offering real-time visibility into critical water system performance and operating conditions.



Remove Contaminants. Optimize Efficiency.

Enabling Water Circularity Through Innovative Approaches

Advanced treatment technologies that remove even the most challenging contaminants that impedes water reclamation and circularity. Removing critical contaminants helps optimize water recycling, operational efficiency and sustainable chip manufacturing.

PEROXIDE REMOVAL

Eliminate residual hydrogen peroxide from process and reclaim streams, enabling downstream water recovery and system stability.

FLUORIDE REMOVAL

Reduce fluoride concentrations in wastewater and reclaim streams, supporting water circularity and environmental compliance.

HEAVY METAL REMOVAL

Extract dissolved metals from semiconductor wastewater, improving water quality and reclaim potential.

PFAS REMOVAL

Advancing innovative approaches to address PFAS-related challenges and support evolving industry needs.

How do you manufacture **more AI chips with less water?**

Together, our technology platforms help semiconductor manufacturers improve wafer quality, optimize operations and advance water circularity.

**Meet stringent water quality
specification. Reclaim more water.
Support reliable performance at scale.**

